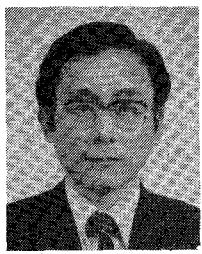


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## Broad-Band Characteristics of EHF IMPATT Diodes

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**Abstract**—Measurements have been made of the oscillator characteristics when a GaAs EHF double-drift IMPATT diode designed for a frequency of 35 GHz is operated over an extended frequency range from 33–50 GHz. The diode which was designed for 35 GHz has a broad-band capability which allows it to produce 2.15 W at 44.1 GHz. An analytic model is shown to predict accurately the observed results. The model indicates that the upper limit in frequency can be increased by reducing the diode area or the series resistance as well as by reducing the length of the drift region.

### I. INTRODUCTION

THE BROAD-BAND characteristics of IMPATT diodes make them a flexible power source for use in many applications. In this paper we describe a theoretical

and experimental study of the power output of a GaAs double-drift diode designed for 35 GHz when it is operated over an extended frequency range from 33–50 GHz.

The diode was operated in a top-hat circuit in which the circuit parameters were varied in order to optimize the output power at a given frequency and dc-current level. The experimental results are compared with calculations based on an analytic model described previously [1]–[4]. This analytic model uses the Read equation to describe the time behavior of the avalanche zone and assumes that the saturation current is small, that ionization in the drift region is negligible, and that the carriers move at saturated velocities. One of the important parameters of the model is the series resistance. In these calculations, we use values measured accurately by a method described elsewhere [5]. The calculated results of the model were then in close agreement with the experimental results. This model allows

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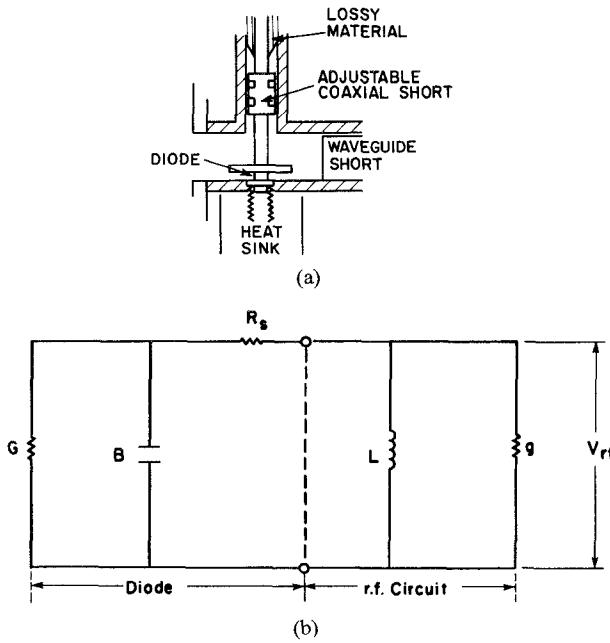


Fig. 1. (a) Sketch of "top-hat" configuration with sliding short. (b) Lumped element equivalent RF circuit for the diode and the external circuit.

us to draw useful conclusions as to the relative importance of different parameters such as drift length, junction area, and series resistance in determining the frequency response of an IMPATT diode.

Diodes were tested with both copper and diamond heat sinks. With the diamond heat sink, a diode designed for 35 GHz produced 2.15W with 14.4-percent efficiency at 44.1 GHz.

## II. EXPERIMENTAL TECHNIQUE

The RF tests were made in a circuit similar to the top-hat circuit described by Misawa [6]. The RF test cavity used in our tests is sketched in Fig. 1. With a given value of the dc current, the circuit was adjusted carefully to obtain the maximum possible output power consistent with the requirement that the oscillation occurred at a specified frequency. Over a small frequency range, one can represent the device operation by the lumped circuit model shown in Fig. 1(b). Here  $G$  and  $B$  are the conductance and susceptance of the IMPATT diode,  $R_s$  is the series resistance,  $L$  is the load inductance which is adjusted to maintain the desired frequency, and  $g$  is the load conductance.

In one type of measurement, the circuit is tuned to maintain a specified frequency while  $I_{dc}$ , the dc current through the diode, is slowly increased. At successive current levels, the tuning is adjusted to give the maximum output power. In terms of the lumped element equivalent circuit of Fig. 1(b), we can picture the load conductance  $g$  being adjusted to give the maximum power while the inductance  $L$  is changed as necessary to maintain the specified frequency. The output power is

$$P_{out} = \frac{1}{2} g V_{rf}^2 \quad (1)$$

while an oscillation can only occur if  $V_{rf}$  can adjust itself to satisfy the condition

$$g = -G - B^2 R_s. \quad (2)$$

Equation (2) is valid in the limit where  $B R_s$  and  $G R_s$  are both small compared to unity. In this limit the  $V_{rf}$  across the diode is nearly the same as the  $V_{rf}$  across the load.

## III. THE ANALYTICAL MODEL

The analytical model for small saturation current, which has been described earlier [2]–[4], is reproduced in the Appendix. For the double-drift GaAs diode used in these experiments, it is an excellent approximation to assume that the drift regions are symmetric. Hereafter, in this paper we assume  $v_n = v_p$  and  $w_n = w_p$  to reduce the algebra, although there is no difficulty in carrying through a more general calculation.

### A. Conditions Near the Oscillation Threshold

At low current levels, where  $\omega_R^2/\omega^2 \ll 1$ , an explicit expression can be obtained for the RF voltage and the optimum load conductance. These expressions are used for illustrating the oscillation process, but at higher currents where the approximation is invalid, we will use a numerical solution for the admittance in (A1).

When  $\omega_R^2/\omega^2 \ll 1$ , the real part of (A1) simplifies to

$$G = -2 \frac{(1 - \cos \theta)}{\theta} \frac{I_{dc}}{V_{rf}} \frac{I_1(b)}{I_0(b)} \quad (3)$$

where  $\theta = \omega w_n/v_n = \omega w_p/v_p$  is the common transit angle and

$$b = \frac{3\alpha' v_s}{\omega w_T} V_{rf}. \quad (4)$$

Near the oscillation threshold,  $b$  is small which allows the modified Bessel functions in (3) to be expanded in a power series, giving

$$G = -\frac{3\alpha'}{2\theta^2} (1 - \cos \theta) I_{dc} \left( 1 - \frac{9}{32} \frac{\alpha'^2}{\theta^2} V_{rf}^2 \right) \quad (5)$$

where terms proportional to  $V_{rf}^4$  and higher powers are neglected.

Oscillation can only occur when the negative conductance exceeds  $B^2 R_s$  in magnitude, which requires  $I_{dc}$  to exceed a threshold value, given by (5) as

$$I_{th} = \frac{2\theta^2 \omega^2 C_d^2 R_s}{3\alpha' (1 - \cos \theta)}. \quad (6)$$

Now, as the dc current increases above the threshold, we continually adjust the load conductance to give the maximum output power, which means that

$$\frac{\partial P_{out}}{\partial g} = 0 \quad (7)$$

where  $P_{out}$  is given by (1). Solving (7) and (2) when  $\Delta I = I_{dc} - I_{th}$  is small compared with  $I_{th}$  gives

$$g = \frac{3\alpha'}{4\theta^2} (1 - \cos \theta) \Delta I \quad (8)$$

and

$$V_{rf}^2 = \frac{16\theta^2}{9\alpha'^2} \frac{\Delta I}{I_{th}} \quad (9)$$

where we have neglected terms proportional to  $\Delta I^2$ . Thus, when  $\Delta I$  is small, the output power increases as

$$P_{out} = \frac{2(1-\cos\theta)}{3\alpha'} \frac{\Delta I^2}{I_{th}}. \quad (10)$$

The power output for the case in which  $g$  is adjusted to maximize the power output can be compared with the case where  $g$  is kept small but constant as the current is increased. Then  $V_{rf}^2$  increases at exactly twice the rate given by (9) while the output power increases linearly with  $\Delta I$ , as has been shown elsewhere [5]. A numerical solution for  $V_{rf}$  near the threshold current is plotted in Fig. 2 as a dashed curve for  $g$  fixed at 0.051 mS and as a solid curve when  $g$  is continually adjusted to optimize the output power. The dotted curve in Fig. 2 is the parabola defined by (9); it can be seen that this approximate formula is virtually identical with the numerical calculation. The threshold calculations were all made for the diode 33637, No. 48, which was assumed to be operating at 35.7 GHz and 50°C. The results are in agreement with experimental measurements for  $g = 0.051$  mS, described elsewhere [5].

### B. Operation at Higher Current Levels

At higher current levels where the threshold approximation loses accuracy, numerical solutions of the analytic model will be used. Moreover, Fig. 2 shows the RF voltage becoming larger as the current increases, while it is usually assumed that the RF voltage cannot become larger than about one-half the dc voltage [7]. For X-band devices, it has already been observed [2] that the measured conductance agrees closely with the conductance calculated from the analytic model for small  $V_{rf}$ , except that the measured conductance falls rapidly below the predicted conductance when  $V_{rf}$  exceeds a critical value which we call  $V_{rfmax}$ . Similarly, the measured conductance for an EHF diode was found to drop abruptly when  $V_{rf}$  exceeded a  $V_{rfmax}$  equal to 11 V, as shown in Fig. 3(a), for measurements taken at 200°C with a 200-mA dc current.

As described elsewhere [2]–[4], these  $G$  versus  $V_{rf}$  curves are generated by first calibrating the “top-hat” circuit  $S$ -parameters using the known capacitance and series resistance of the chip biased below breakdown and then using these  $S$ -parameters to calculate  $G$  from the measured reflection coefficients when the diode is generating microwave power.

The electric field profile for the diode in Fig. 3(a) at room-temperature breakdown is shown in Fig. 3(b), based on a computer reconstruction using data at various etch depths measured by a  $CV$  digital profilometer. The measurements described below were on wafer 33637 which has a profile similar to Fig. 3(b). Therefore, we will assume that at 200°C, the diodes from this wafer will also have  $V_{rfmax}$  equal to 11 V. Adlerstein and Moore [4] found good agreement with experimental measurements when they as-

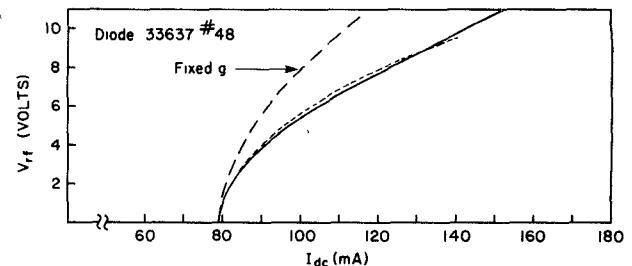


Fig. 2. Calculated RF voltage versus current near threshold conditions. Dashed curve: fixed  $g = 0.051$  mS; solid curve:  $g$  varied to maximize output power; dotted curve: threshold approximation.  $f = 35.7$  GHz.

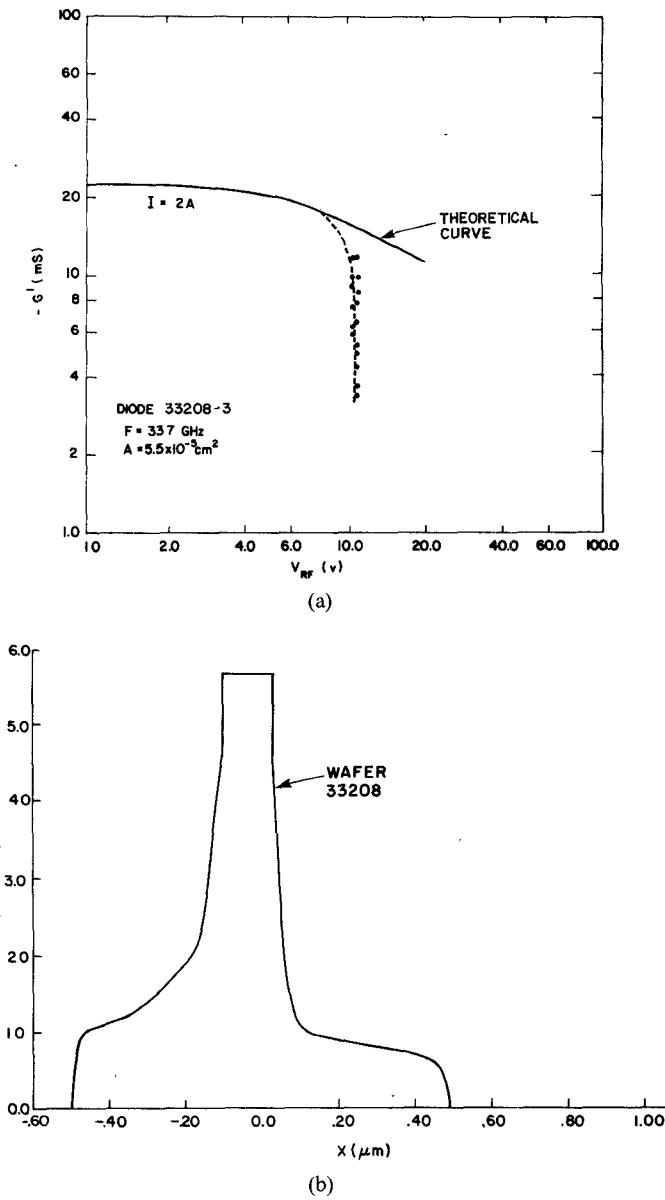


Fig. 3. (a) Negative conductance versus RF voltage. The measured points (·) are compared to theoretical calculations. (b) Electric field profile at room temperature breakdown based on computerized reconstruction from  $CV$  data.

sumed that  $V_{rfmax}$  scaled with temperature in proportion to the measured variation of the breakdown voltage. At 200°C, the breakdown voltage is 19.4 V so that a  $V_{rfmax}$  of 11 V is 57 percent of the breakdown voltage, which is comparable

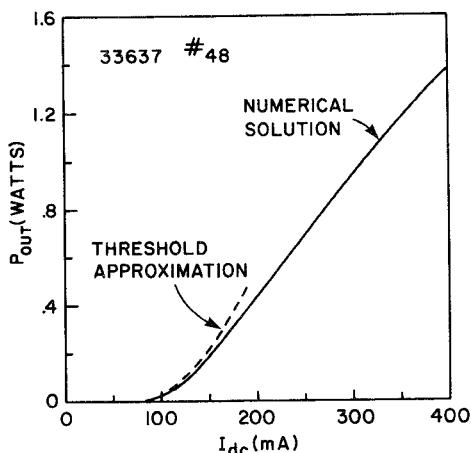


Fig. 4. Calculated output power versus current.  $f = 35.7$  GHz,  $T = 50^\circ\text{C}$ .  $V_{\text{rf}} = V_{\text{rfmax}} = 11$  V for  $I_{\text{dc}}$  above 152 mA.

to the ratio of 50 percent that Read originally suggested [7].

According to the numerical results plotted in Fig. 2,  $V_{\text{rf}}$  increases rapidly as the current is increased above the threshold value and approaches 11 V near 152 mA. In Fig. 4, the solid curve shows the results of a numerical solution of the analytical model when  $g$  is varied to optimize the power output while  $V_{\text{rf}}$  is constrained to be less than 11 V. The dashed curve in Fig. 4, which was calculated from the threshold approximation of (10), is close to the numerical result until the dc current exceeds 200 mA.

#### IV. MEASUREMENTS OF OUTPUT POWER VERSUS FREQUENCY

Measurements of maximum output power versus frequency for a fixed dc current were made on the two diodes listed in Table I. The values of  $R_s$  given in the table were measured by the threshold method [5]. For each of these experiments, the expected maximum power was calculated by a numerical solution of the analytic model assuming  $V_{\text{rfmax}} = 11$  V. The physical characteristics used in calculations for wafer 33637 are given in Table II. The velocities and ionization coefficients were based on measurements in [8] and [9]. Although the values in Table II are given for  $200^\circ\text{C}$ , they were changed appropriately when calculations were made at other temperatures.

The measurements for the device 33637, No. 9 are shown in Fig. 5. The device has a copper heat sink so that at 360 mA the diode is thermally limited, as indicated by the values of  $\Delta T_j$  shown in the figure. The calculations, which assumed a diode temperature of  $270^\circ\text{C}$ , agree closely with the experiment. In making these comparisons it is assumed that the top-hat circuit has 100-percent efficiency.

Similar measurements were taken on wafer 33637, No. 48, as shown in Fig. 6. Because this diode had a diamond heat sink, the dc current could be increased to 500 mA while maintaining satisfactory values of  $\Delta T_j$ . This device had a series resistance of  $0.39\ \Omega$  compared with  $0.17\ \Omega$  for the copper heat sink, so that it produced less power when operated at the same dc current. For example, at 360 mA, the output at 44 GHz dropped from 0.94 W to 0.82 W.

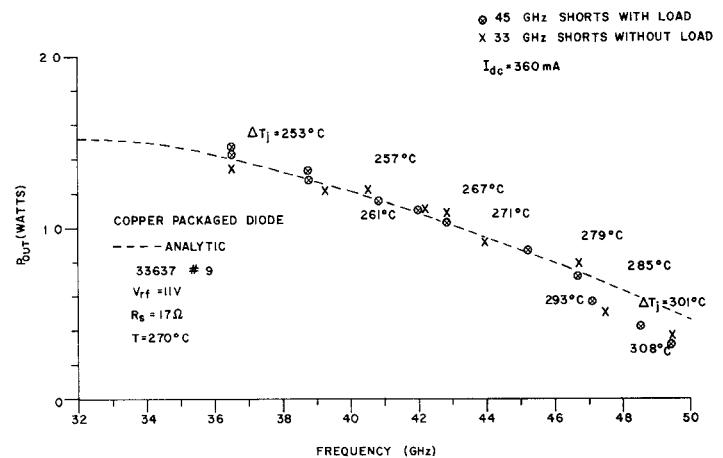


Fig. 5. Measured and calculated output power versus frequency for diode 33637, no. 9.  $\Delta T_j$  is listed for the experimental points. Dashed curve: numerical calculation assuming  $V_{\text{rfmax}} = 11$  V and  $T = 270^\circ\text{C}$ .

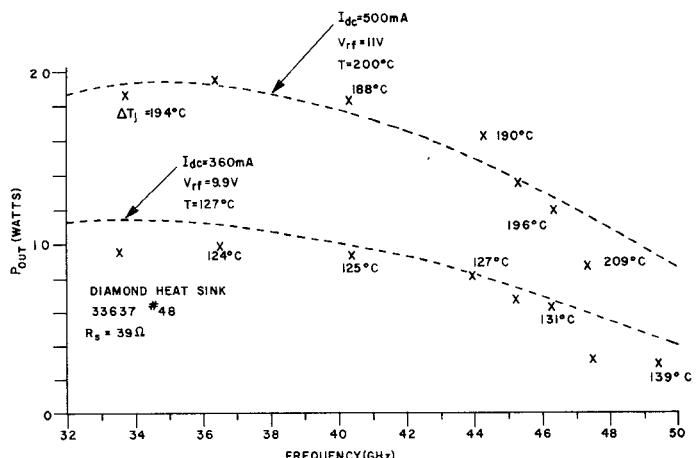


Fig. 6. Measured and calculated output power versus frequency for diode 33637, no. 48. (X) Experimental points. The dashed curves are calculated for 500 mA ( $V_{\text{rf}} = 11$  V,  $T = 200^\circ\text{C}$ ) and for 360 mA ( $V_{\text{rf}} = 9.9$  V,  $T = 127^\circ\text{C}$ ).  $\Delta T_j$  is listed for the experimental points.

TABLE I  
MEASURED DEVICE CHARACTERISTICS

Diode	$A (10^{-5}\text{ cm}^2)$	$\theta (\text{ }^\circ\text{C/W})$	$R_s (\Omega)$
33637 No. 9	7.04	34.9	0.17
33637 No. 48	6.14	18.8	0.39

TABLE II  
PHYSICAL CHARACTERISTICS OF WAFER 33637 AT  $200^\circ\text{C}$

$w_n = w_p = 0.48\ \mu\text{m}$
$w_a = 0.18\ \mu\text{m}$
$E_{AV} = 5.8 \times 10^5\ \text{V/cm}$
$v_n = v_p = 4.7 \times 10^6\ \text{cm/sec}$
$\alpha = 5.6 \times 10^4\ \text{cm}^{-1}$
$\alpha' = 0.225\ \text{V}^{-1}$

However, at 500 mA the diamond package produced 1.5 W with a  $\Delta T_j$  of only  $190^\circ\text{C}$ .

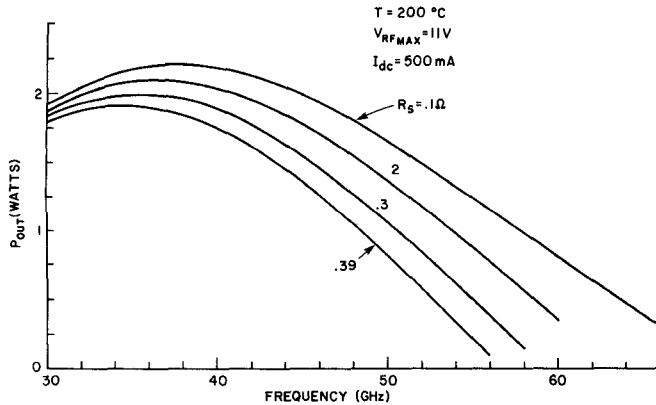


Fig. 7. Calculated output power versus frequency. The calculations of Fig. 6 for 500 mA are modified by assuming the series resistance is reduced to the indicated values.

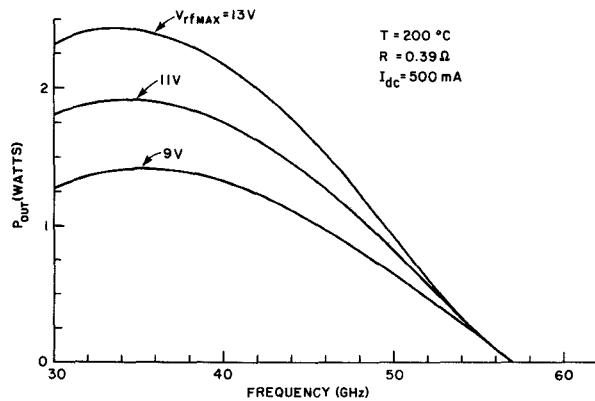


Fig. 8. Calculated output power versus frequency. The calculations of Fig. 6 for 500 mA are modified by assuming  $V_{rfmax}$  is changed to the indicated values.

For the numerical calculation,  $V_{rfmax}$  was kept at 11 V for the 500-mA case but, assuming it decreases in proportion to the breakdown voltage at lower temperatures, it was taken to be 9.9 V for the 360-mA curve. The material characteristics were evaluated at 200°C for 500 mA and at 127°C for 360 mA. For both curves, the agreement between theory and experiment is very close.

Although the numerical solution is needed for accurate results, the diode behavior can be better understood from approximate relations. Therefore, assume  $\omega_R^2/\omega^2 \ll 1$ ; this is not a bad approximation under the conditions of Figs. 5 and 6 and since  $\omega_R^2$  is fixed for fixed  $V_{rf}$  and  $I_{dc}$ , the approximation becomes better at higher frequencies. Then, we neglect terms proportional to  $\omega_R^2/\omega^2$  in (A1), and obtain from the oscillation requirement of (2)

$$g = \frac{(1 - \cos \theta)}{\theta} C_d \frac{\omega_R^2}{\omega} - \omega^2 C_d R_s. \quad (11)$$

The power will drop as the frequency increases until  $g = 0$  at the cutoff frequency

$$f_c = \frac{1}{2\pi} \left( \frac{(1 - \cos \theta)}{\theta} \frac{\omega_R^2}{C_d R_s} \right)^{1/3}. \quad (12)$$

Near the cutoff frequency,  $(1 - \cos \theta)/\theta$  can generally be approximated as  $2/\pi$  for values of  $R_s$  greater than 0.2 Ω.

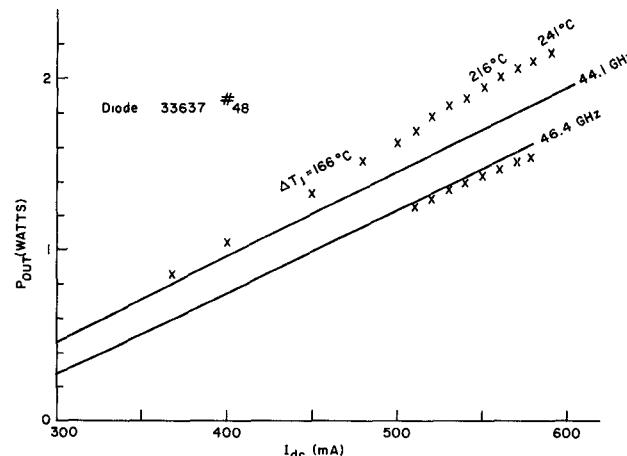


Fig. 9. Measured and calculated output power versus current for 44.1 and 46.4 GHz. The calculations assume  $V_{rfmax} = 11$  V and  $T = 200^\circ\text{C}$ .  $\Delta T_j$  is listed for several experimental points.

Moreover, near cutoff,  $V_{rf}$  will approach zero so that  $\omega_R^2$  approaches the avalanche frequency  $\omega_a^2$ . Thus, the cutoff frequency is proportional to the  $1/3$  power of  $I/R_s$  and, for fixed current, the cutoff frequency is proportional to  $A^{-2/3}$ .

The analytical model allows us to calculate the effect of making specific changes in diode parameters. For example, Fig. 7 shows the effect of reducing  $R_s$  from the value of 0.39 Ω used in Fig. 6 to 0.3, 0.2, and 0.1 Ω. Since we are now able to produce diamond heat sinks with  $R_s$  less than 0.2 Ω, we should be able to obtain higher powers and wider bandwidth as indicated by the figure.

The effect of changing  $V_{rfmax}$  to 9 and 13 V from the original value of 11 V used in the earlier calculations is shown in Fig. 8. An increase in  $V_{rfmax}$  increases the output power at intermediate frequencies, but it does not increase the cutoff frequency since  $V_{rf}$  drops below  $V_{rfmax}$  and approaches zero as the cutoff frequency is approached.

The junction temperatures shown in Figs. 5 and 6 are nearly constant as a function of frequency, although it can be seen that they increase slightly as the RF output power drops so that more input power must be dissipated as heat. The values of  $\Delta T_j$  shown in Figs. 5 and 6, were based on the measured dissipated power using values of thermal resistance measured by a technique similar to that described by Haitz [10].

## V. MEASUREMENTS OF OUTPUT POWER VERSUS DC CURRENT

Since the diode with the diamond heat sink was not thermally limited at 500 mA, one can choose a particular frequency and push the dc current higher. The output powers measured at 44.1 GHz and at 46.4 GHz are indicated by the crosses in Fig. 9, while the solid curves are calculated from the numerical model assuming  $V_{rfmax} = 11$  V and a temperature of 200°C.

As the current is increased, the output power increases in fairly good agreement with the calculated power. However, attempts to push the power level beyond 590 mA for the 44.1-GHz experiment led to a rapid drop in the output

power. At present it is not clear whether this is associated with a threshold for instability for subharmonic oscillations [11], [12], or whether we have reached the largest value of conductance achievable with the given operating frequency and diode capacitance.

The power output at 44.1 GHz reached a maximum of 2.15 W and 14.4-percent efficiency at 590 mA.

## VI. CONCLUSIONS

Power output over a frequency band from 33–50 GHz has been demonstrated and shown to agree with the results calculated from an analytical model using experimentally demonstrated values for  $R_s$  and  $V_{rfmax}$ . In particular, it was not necessary to invoke the negative differential conductivity of  $n$ -GaAs, the RF motion of the depletion edge, nor drift region ionization in order to explain the high power results.

The power output of these diodes is dependent on  $V_{rfmax}$ , whose value has been measured experimentally but whose determination is imperfectly understood. Nevertheless, it seems plausible that the high mobility of electrons at low fields in GaAs and the appropriately designed lo-hi-lo Read or hybrid profile which avoids drift-region ionization while keeping carrier velocities saturated at moderate RF swings, have helped us to attain the relatively high values of  $V_{rf}$  which produced the good efficiency and power which we have measured in this study.

The experiments also showed that somewhat higher CW power could be obtained with improved heat sinking. However, even in the absence of a thermal limitation, the output power was limited because it saturated abruptly at a critical current. A similar situation occurred in X-band diodes when the thermal limitation was effectively removed by going to pulsed operation [3]. The achievement of even higher output power would become possible if circuits could be designed to increase this critical current or if  $V_{rfmax}$  could be increased. Improvements in technology, since the experiments described in this paper, have already resulted in diamond-packaged EHF diodes with thermal resistances less than  $15^\circ\text{C}/\text{W}$  and with series resistance on the order of  $0.2 \Omega$  or less. These improvements will allow some increase in output power without changing the doping profile or the external circuit.

## APPENDIX

### THE ANALYTIC READ DIODE MODEL

The analytical model [1]–[4] expresses the admittance  $Y = G + jB$  as

$$Y = \frac{j\omega C_d (1 - \omega_R^2/\omega^2)}{1 - \frac{\omega_R^2}{\omega^2} \left( \frac{w_n}{w_T} (1 + F_n) + \frac{w_p}{w_T} (1 + F_p) \right)} \quad (\text{A1})$$

where the angular resonance frequency is

$$\omega_R^2 = h(b) \omega_a^2 \quad (\text{A2})$$

where  $\omega_a$  is the usual avalanche frequency

$$\omega_a^2 = \frac{3\alpha' v_s}{\epsilon} j_{dc} \quad (\text{A3})$$

where  $j_{dc}$  is the current density,  $\alpha'$  is the derivative of the ionization coefficient with respect to field,  $\epsilon$  is the dielectric constant, and  $v_s = 2v_n v_p / (v_n + v_p)$ , where  $v_n$  and  $v_p$  are the saturated carrier velocities. The quantity  $b$  is a nondimensional form of the RF voltage

$$b = \frac{3\alpha' v_s}{\omega w_T \gamma} V_{rf} \quad (\text{A4})$$

where  $\gamma$ , which is normally close to unity, is given by

$$\gamma^2 = \left[ 1 - \frac{\omega_R^2}{\omega^2} \left( \frac{w_n}{w_T} \left( 1 - \frac{\sin \theta_n}{\theta_n} \right) + \frac{w_p}{w_T} \left( 1 - \frac{\sin \theta_p}{\theta_p} \right) \right) \right]^2 + \left[ \frac{\omega_R^2}{\omega^2} \left( \frac{w_n}{w_T} \left( \frac{1 - \cos \theta_n}{\theta_n} \right) + \frac{w_p}{w_T} \left( \frac{1 - \cos \theta_p}{\theta_p} \right) \right) \right]^2. \quad (\text{A5})$$

Also

$$F_n = \frac{e^{-j\theta_n} - 1}{j\theta_n}$$

and  $\theta_n = \omega w_n / v_n$  and similarly for  $F_p$  and  $\theta_p$ . The diode capacitance  $C_d = \epsilon A / w_T$  and  $w_T$  and  $w_T = w_n + w_p$  is the total width of the diode.

Assuming that the saturation current is negligible, the function  $h(b)$  in (A2) is

$$h(b) = \frac{2I_1(b)}{bI_0(b)}$$

where  $I_0$  and  $I_1$  are the modified Bessel functions of order 0 and 1.

Given  $b$  and  $j_{dc}$ , as well as the physical parameters of the diode, (A1)–(A5) can be solved explicitly to give  $Y$  and  $V_{rf}$ . The numerical solution, with  $V_{rf}$  and  $j_{dc}$  given, is obtained by iterating the calculation which converges rapidly to the correct values  $b$  and  $Y$ .

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## A Multiple-Device Cavity Oscillator Using Both Magnetic and Electric Coupling Mechanisms

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**Abstract**—This paper presents a novel concept to increase the number of active devices combined in a cavity oscillator by coupling them to both electric and magnetic fields inside the cavity. The structure employs probes and coaxial lines for electric and magnetic coupling, respectively. The sum of the output powers from individual devices combined can be obtained by properly adjusting the coupling factors of the circuit. Operation principles of the circuit are analyzed for probe coupling, and results are applied to

explain the operation of the circuit when both probe and coaxial coupling are used. The circuits described here are free from moding instabilities. Prototype circuits have been constructed at *X*-band, using Gunn diodes, for experimental confirmation of the theory developed.

### I. INTRODUCTION

THE SINGLE-TUNED oscillators invented by Kurokawa *et al.* [1] and Harp *et al.* [2] have received considerable development and application as the most successful power combining techniques at microwave and millimeter-wave frequencies [3]–[7]. Nevertheless, the increasing need for higher and higher output power may

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